

# Citations for Target : Ta205

<b>Pub. Year</b>	<b>Authors, Title, Journal Citation and Comments</b>	<b>Citation Numb</b>
<b>1973</b>	Behrisch, R. Schertzer, B. M. U. <b>'Rutherford Backscattering as a Tool to Determine Electronic Stopping Powers in Solids'</b> <i>Thin Solid Films, 19, 247-257 (1973)</i> Comment : S. 50-150 keV H -> Nb, Ta, Ta <sub>2</sub> O <sub>5</sub>	<b>1973-Behr</b> 0508
<b>1973</b>	Phillips, D. Pringle, J. P. S. <b>'Surface Effects in the Measurement of Range Profiles by Oxide Dissolution'</b> <i>J. Electrochem. Soc., 120, 1067-66 (1973)</i> Comment : R, dR. 5, 40 keV Tl, Au -> Ta <sub>2</sub> O <sub>5</sub>	<b>1973-Phil</b> 0686
<b>1974</b>	Pringle, J. P. S. <b>'Range Profiles for Ions Implanted into Anodic Tantalum Oxide'</b> <i>J. Electrochem. Soc., 121, 45-55 (1974)</i> Comment : R. 0.5-160 keV 24Na, 42K, 86Rb, 125Xe, 134Cs, 204Tl, 222Rn -> Ta <sub>2</sub> O <sub>5</sub>	<b>1974-Prin2</b> 0228
<b>1976</b>	Bottiger, J. Rud, J. R. Leslie and N. <b>'Range Profiles of 6-16-keV Hydrogen Ions Implanted in Metal Oxides'</b> <i>J. Appl. Phys., 47, 1672-75 (1976)</i> Comment : R, dR. 6-16 keV H -> Al <sub>2</sub> O <sub>3</sub> , Nb <sub>2</sub> O <sub>5</sub> , Ta <sub>2</sub> O <sub>5</sub>	<b>1976-Bott2</b> 0797
<b>1976</b>	Pringle, J. P. S. <b>'A Comparison of Sectioning Methods used to Measure Concentration Profiles in Anodic Oxides'</b> <i>Can. J. Phys., 54, 56-65 (1976)</i> Comment : R, dR. (10-160 keV) Na, Ar, K, Kr, Xe -> Al <sub>2</sub> O <sub>3</sub> , Ta <sub>2</sub> O <sub>5</sub> , WO <sub>3</sub> , Ta <sub>2</sub> O <sub>5</sub>	<b>1976-Prin</b> 0819
<b>1976</b>	Schertzer, B. M. U. Borgesen, P. Nicolet, M. -A. Mayer, J. W. <b>'Determination of Stopping Cross Sections by Rutherford Backscattering'</b> <i>O. Meyer, G. Linker, F. Kappeler (Ed.): Ion Beam Surface Layer Analysis. Plenum, N. Y., 33-46 (1976)</i> Comment : S. 0.2-2.0 MeV He -> Au, Pt, Ta <sub>2</sub> O <sub>5</sub> , SiO <sub>2</sub>	<b>1976-Sche</b> 0786
<b>1978</b>	Moller, W. <b>'Background Reduction in D(3He,alpha)H Depth Profiling Experiments using a Simple Electrostatic Deflector'</b> <i>Nucl. Inst. Methods, 157, 223-227 (1978)</i> Comment : R, dR. 20 keV D -> Al <sub>2</sub> O <sub>3</sub> , Ta <sub>2</sub> O <sub>5</sub>	<b>1978-Moll</b> 1163
<b>1978</b>	Stephens, K. G. Wilson, I. H. <b>'Properties and Applications of Ion-Implanted Films'</b> <i>Thin Solid Films, 50, 325-347 (1978)</i> Comment : R. 30 keV O -> Ta <sub>2</sub> O <sub>5</sub> , 60-80 keV Ar -> Ta	<b>1978-Step</b> 1242

# Citations for Target : Ta2O5

Pub. Year	Authors, Title, Journal Citation and Comments	Citation Numb
1979	Ishii, K. Blondiaux, G. Valladon, M. Debrun, D. L. <b>'The Study of Stopping Powers by the Method of the Average Stopping Power'</b> <i>Nucl. Inst. Methods, 158, 199-203 (1979)</i> Comment : S. T (3MeV) -> BeO, Al2O3, SiO2, TiO2, ZnO, Nb2O5, Ta2O5	1979-Ishi 1539
1980	Blondiaux, G. Valladon, M. Ishii, K. Debrun, J. L. <b>'Search for the Influence of Chemical Effect on the Stopping Power: the Case of Oxides'</b> <i>Nucl. Inst. Methods, 168, 29-31 (1980)</i> Comment : S, dS. .5-2.5 MeV H -> BeO, Al2O3, TiO2, Zno, Nb2O5, Ta2O5	1980-Blon 1314
1983	Hautala, M. Paltemaa, R. Anttila, A. Luomajarvi, M. <b>'Ion Range Distributions in Oxides'</b> <i>Nucl. Inst. Methods, 209/210, 37-41 (1983)</i> Comment : R. N(20-100 keV) -> SiO2, MoO3, Ta2O5	1983-Haut 2020
1997	Moon, D. W. Kim, H. K. Kim, Y. P. Ha, Y. H. Choi, S. K. <b>'The Electronic Energy Loss of 100 keV Heavy Ions in Medium Energy Ion Scattering Analysis of Ta2O5 Ultrathin Film'</b> <i>Nucl. Inst. Methods, B125, 120-123 (1997)</i> Comment : S. Li, N, Ne (100 keV) -> Ta2O5	1997-Moon 2238